



ITW

Rev. 04/03

Docket No. ELM-1 Cont. 10

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Glenn J. Leedy
Application No.: 10/700,429 Confirmation No.: 5639
Filed : November 3, 2003
For : MEMBRANE IC FABRICATION (AS AMENDED)
Group Art Unit : 3729
Examiner : Not yet assigned

New York, New York
July 8, 2004

Hon. Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

TRANSMITTAL LETTER FOR
INFORMATION DISCLOSURE STATEMENT

Sir:

Transmitted herewith is an Information Disclosure
Statement in the above-identified application. This
Statement is submitted:

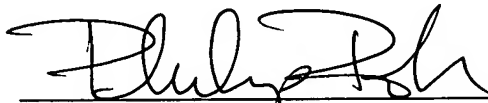
- ☐ within three months of the application filing date;
- ☒ more than three months from the application filing date but before the mailing date of the first Office Action on the merits.

In accordance with 37 C.F.R. § 1.97, submission of this Statement requires no fee. However, if for any reason a fee is due, the Director is hereby authorized to charge payment of any fees required in connection with this

Information Disclosure Statement to Deposit Account

No. 06-1075. A duplicate copy of this letter is transmitted herewith.

Respectfully submitted,



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Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450 on

July 8, 2004
Claire J. Saint-Jean Goodman

Signature of Person Signing



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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P.O. Box 1450
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INFORMATION DISCLOSURE STATEMENT

Sir:

In accordance with 37 C.F.R. §§ 1.56 and 1.97,
applicant wishes to call the attention of the Examiner to
the following documents:

U.S. Patents

Fujii et al.	Re. 34,893	04/04/95
Foster	2,915,722	12/01/59
Farrand	3,202,948	08/24/65
Lesk	3,559,282	02/02/71
Burkhardt	3,560,364	02/02/71
Emmasingel	3,602,982	09/07/71
Medicus	3,615,901	10/26/71
Napoli et al.	3,716,429	02/13/73
Krishna et al.	3,777,227	12/14/73
Kuipers	3,868,565	02/25/75
Yerman	3,922,705	11/25/75
Wanlass	3,997,381	12/14/76
Stein	4,070,230	01/24/78

Greenwood et al.	4,131,985	01/02/79
Hauser, Jr., et al.	4,142,004	02/27/79
Hoeberechts	4,251,909	02/24/81
Kubacki	4,262,631	04/21/81
Shioya et al.	4,394,401	07/19/83
Trenkler et al.	4,401,986	08/30/83
Thomas et al.	4,416,054	11/22/83
Takagi et al.	4,539,068	09/03/85
Reid et al.	4,585,991	04/29/86
Yasumoto et al.	4,612,083	09/16/86
Belanger et al.	4,617,160	10/14/86
Shimizu et al.	4,618,397	10/21/86
Schmitz	4,618,763	10/21/86
Christensen	4,663,559	05/05/87
Burns et al.	4,684,436	08/04/87
Hatada	4,693,770	09/15/87
Maeda et al.	4,702,336	10/27/87
Seibert et al.	4,702,936	10/27/87
Go	4,706,166	11/10/87
Stevenson	4,721,938	01/26/88
Reid	4,761,681	08/02/88
Holmen et al.	4,784,721	11/15/88
Freeman	4,810,673	03/07/89
Mattox et al.	4,825,277	04/25/89
Tam et al.	4,857,481	08/15/89
Leedy	4,924,589	05/15/90
Borel et al.	4,940,916	07/10/90
Borel et al.	ReB14,940916	11/26/96
Vranish et al.	4,950,987	08/21/90
Lee et al.	4,952,446	08/18/90
Rokos	4,954,865	09/04/90
Shinomiya	4,957,882	09/18/90
Young et al.	4,965,415	10/23/90
Mauger	4,966,663	10/30/90
Leedy	4,994,735	02/19/91
Keogh et al.	5,008,619	04/16/91
Allen et al.	5,010,024	04/23/91
Leedy	5,020,219	06/04/91
Leedy	5,034,685	07/23/91
Greenwald et al.	5,070,026	12/03/91
Findler et al.	5,071,510	12/10/91
Machado et al.	5,098,865	03/24/92
Leedy	5,103,557	04/14/92
Mauger	5,110,373	05/05/92
Eichelberger	5,111,278	05/05/92
Chan et al.	5,116,777	05/26/92
Miller	5,130,894	07/14/92

Roy	5,132,244	07/21/92
Hadwin	5,151,775	09/29/92
Henager, Jr., et al.	5,156,909	10/20/92
Zimmerman	5,203,731	04/20/93
Leedy	5,225,771	07/06/93
Bower et al.	5,236,118	08/17/93
Bureau et al.	5,262,351	11/16/93
Bertin et al.	5,270,261	12/14/93
Sanders	5,273,940	12/28/93
Tuckerman	5,274,270	12/28/93
Chebi et al.	5,279,865	01/18/94
Nakanishi et al.	5,284,796	02/08/94
Leedy	5,323,035	06/21/94
Wojnarowski	5,324,687	06/28/94
Leedy	5,354,695	10/11/94
MacDonald	5,363,021	11/08/94
Goossen	5,385,632	01/31/95
Nelson et al.	5,385,909	10/25/94
Shimoji	5,420,458	05/30/95
Miyake	5,424,920	06/13/95
Finnila	5,426,072	06/20/95
Akagi et al.	5,426,363	06/20/95
Yasohama et al.	5,432,444	07/11/95
Carson et al.	5,432,729	07/11/95
Hauck et al.	5,434,500	07/18/95
Leedy	5,451,489	09/19/95
Leedy	5,453,404	09/26/95
Gurtler et al.	5,457,879	10/17/95
Naruse	5,476,813	12/19/95
Gates	5,489,554	02/06/96
Bertin et al.	5,502,667	03/26/96
Leedy	5,512,397	04/30/96
Pati et al.	5,527,645	06/18/96
Koskenmaki et al.	5,529,829	06/25/96
Frye et al.	5,534,465	07/09/96
Toshiaki et al.	5,555,212	09/10/96
Ramm et al.	5,563,084	10/08/96
Leedy	5,571,741	11/05/96
Leedy	5,580,687	12/03/96
Ludwig et al.	5,581,498	12/03/96
Pierrat	5,582,939	12/10/96
Hornbeck	5,583,688	12/10/96
Leedy	5,592,007	01/07/97
Leedy	5,592,018	01/07/97
Heijboer	5,595,933	01/27/97
Noda	5,606,186	02/25/97
Tennant et al.	5,627,112	05/06/97

Leedy	5,629,137	05/13/97
Leedy	5,633,209	05/27/97
Val	5,637,536	06/10/97
Leedy	5,654,127	08/05/97
Leedy	5,654,220	08/05/97
Hudak et al.	5,656,552	08/12/97
Chen et al.	5,675,185	10/07/97
Ohara et al.	5,694,588	12/02/97
Leedy	5,725,995	03/10/98
Weise et al.	5,750,211	05/12/98
Bozso et al.	5,760,478	06/02/98
Okonogi	5,773,152	06/30/98
Rolfson	5,786,116	07/28/98
Zavracky et al.	5,793,115	08/11/98
Ray	5,831,280	11/03/98
Leedy	5,834,334	11/10/98
Leedy	5,840,593	11/24/98
Ito et al.	5,856,695	01/05/99
Sotokawa et al.	5,868,949	02/09/99
Leedy	5,869,354	02/09/99
Sweatt et al.	5,870,176	02/09/99
Davidson	5,880,010	03/09/99
Field et al.	5,882,532	03/16/99
Hübner	5,902,118	05/11/99
Leedy	5,915,167	06/22/99
Leedy	5,946,559	08/31/99
Leedy	5,985,693	11/16/99
Cutter et al.	5,998,069	12/07/99
Leedy	6,008,126	12/28/99
Leedy	6,020,257	02/01/00
Houston	6,045,625	04/04/00
Adamic, Jr.	6,084,284	07/04/00
Gardner et al.	6,097,096	08/01/00
Leedy	6,133,640	10/17/00
Tayanaka	6,194,245 B1	02/27/01
Aleshin et al.	6,197,456 B1	03/06/01
Leedy	6,208,545 B1	03/27/01
Patti	6,236,602 B1	05/22/01
Lin	6,261,728 B1	07/17/01
Leedy	6,288,561 B1	09/11/01
Leedy	6,294,909 B1	09/11/01

Foreign Patents

PCT	WO 98/19337	05/1998
UK	GB 2,215,168	09/1989
EPO	EP 0 189 976	08/1986

EPO	EP 0 731 525	09/1996
FRANCE	2641129	12/1988
JAPAN	JP 60-74643	04/1985
JAPAN	JP 02-082564	03/1990
JAPAN	JP 04-083371	03/1992
JAPAN	JP 04-107964	04/1992
JAPAN	JP 402027600A	01/1990

Other Documents

"IC Tower Patent: Simple Technology Receives Patent on the IC Tower, a Stacked Memory Technology,"
<http://www.simpletech.com/whatsnew/memory/@60824.htm> (1998).

Alloert, K., et al., "A Comparison Between Silicon Nitride Films Made by PCVD of N_2-SiH_4 / A_r and N_2-SiH_4/He ," Journal of the Electrochemical Society, Vol. 132, No. 7, pp. 1763-1766, (July 1985).

Hendricks, et al., "Polyquinoline Coatings and Films: Improved Organic Dielectrics for IC's and MCM's," Eleventh IEEE/CHMT International Electronics Manufacturing Technology Symposium," pp. 361-265 (1991).

Knolle, W.R., et al., "Characterization of Oxygen-Doped, Plasma-Deposited Silicon Nitride," Journal of the Electrochemical Society, Vol. 135, No. 5, pp. 1211-1217, (May 1988).

Nguyen, S.V., "Plasma Assisted Chemical Vapor Deposited Thin Films for Microelectronic Applications, J. Vac. Sci. Technol. Vol. B4, No. 5, pp.1159-1167, (Sep/Oct. 1986).

Olmer, et al., "Intermetal Dielectric Deposition by Plasma Enhanced Chemical Vapor Deposition," Fifth IEEE/CHMT International Electronic Manufacturing Technology Symposium - Design-to-Manufacturing Transfer Cycle," pp. 98-99 (1988).

Runyan, W.R., "Deposition of Inorganic Thin Films," *Semiconductor Integrated Circuit Processing Technology*, p. 142 (1990).

Sze, S.M., "Surface Micromachining," *Semiconductor Sensors*, pp. 58-63 (1994).

Vossen, John L., "Plasma-Enhanced Chemical Vapor Deposition," *Thin Film Processes II*, pp. 536-541 (1991).

Wolf, Stanley, "Basic of Thin Films," *Silicon Processing for the VLSI Era*, pp. 115, 192-193 and 199 (1986).

Copies of the aforementioned documents are listed on the accompanying Form PTO-1449 (submitted in duplicate).

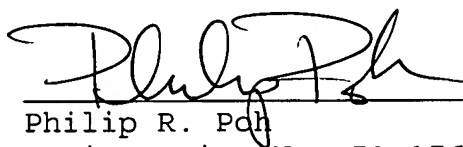
It is respectfully requested that these documents be:

(1) fully considered by the Patent and Trademark Office during the examination of this application; and (2) printed on any patent which may issue on this application.

Applicant requests that a copy of Form PTO-1449, as considered and initialized by the Examiner, be returned with the next communication.

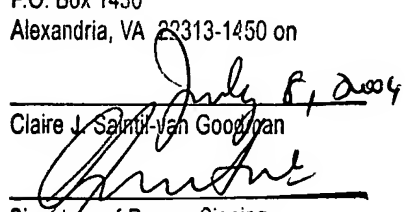
Consideration of the foregoing in relation to this patent application is respectfully requested.

Respectfully submitted,

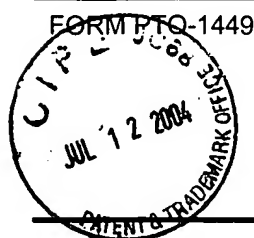


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Claire J. Saint-Van Gooyen


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FORM PTO-1449

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEINFORMATION DISCLOSURE
STATEMENT BY APPLICANTATTY. DOCKET NO.
ELM-1 Cont. 10APPLICATION NO.
10/700,429APPLICANT
Glenn J. LeedyCONFIRMATION NO.
5639FILING DATE
November 3, 2003GROUP
3729

U.S. PATENT DOCUMENTS

EXAMINE R INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	Re. 34,893	04/04/95	Fujii et al.	257	419	
	2,915,722	12/01/59	Foster	336	115	
	3,202,948	08/24/65	Farrand	336	115	
	3,559,282	02/02/71	Lesk	438	113	
	3,560,364	02/02/71	Burkhardt	324	207.12	
	3,602,982	09/07/71	Emmasingel	29	577	
	3,615,901	10/26/71	Medicus	148	11.5 R	
	3,716,429	02/13/73	Napoli et al.	156	17	
	3,777,227	12/14/73	Krishna et al.	257	578	
	3,868,565	02/25/75	Kuipers	324	207.26	
	3,922,705	11/25/75	Yerman	357	26	
	3,997,381	12/14/76	Wanlass	156	3	
	4,070,230	01/24/78	Stein	156	657	
	4,131,985	01/02/79	Greenwood et al.	29	580	
	4,142,004	02/27/79	Hauser, Jr. et al.	438	792	
	4,251,909	02/24/81	Hoeberechts	29	580	
	4,262,631	04/21/81	Kubacki	118	723MP	
	4,394,401	07/19/83	Shioya et al.	427	574	
	4,401,986	08/30/83	Trenkler et al.	340	870.32	
	4,416,054	11/22/83	Thomas et al.	29	572	
	4,539,068	09/03/85	Takagi et al.	156	614	
	4,585,991	04/29/86	Reid et al.	324	158 P	
	4,612,083	09/16/86	Yasumoto et al.	156	633	
	4,617,160	10/14/86	Belanger et al.	264	40.1	
	4,618,397	10/21/86	Shimizu et al.	156	628	
	4,618,763	10/21/86	Schmitz	250	211R	
	4,663,559	05/05/87	Christensen	313	336	
	4,684,436	08/04/87	Burns et al.	216	65	
	4,693,770	09/15/87	Hatada	156	151	

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not conformance and not considered. Include copy of this form with next communication to applicant.

FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO. ELM-1 Cont. 10	APPLICATION NO. 10/700,429
	APPLICANT Glenn J. Leedy	CONFIRMATION NO. 5639
	FILING DATE November 3, 2003	GROUP 3729

	4,702,336	10/27/87	Maeda et al.	180	197	
	4,702,936	10/27/87	Seibert et al.	427	583	
	4,706,166	11/10/87	Go	361	403	
	4,721,938	01/26/88	Stevenson	338	4	
	4,761,681	08/02/88	Reid	357	68	
	4,784,721	11/15/88	Holmen et al.	156	647	
	4,810,673	03/07/89	Freeman	438	386	
	4,825,277	04/25/89	Mattox et al.	257	639	
	4,857,481	08/15/89	Tam et al.	438	619	
	4,924,589	05/15/90	Leedy	438	6	
	4,940,916	07/10/90	Borel et al.	313	306	
	Re B14,940,916	11/26/96	Borel et al.	315	306	
	4,950,987	08/21/90	Vranish et al.	324	207.23	
	4,952,446	08/18/90	Lee et al.	428	220	
	4,954,865	09/04/90	Rokos	257	378	
	4,957,882	09/18/90	Shinomiya	438	65	
	4,965,415	10/23/90	Young et al.	200	83 N	
	4,966,663	10/30/90	Mauger	205	656	
	4,994,735	02/19/91	Leedy	324	158	
	5,008,619	04/16/91	Keogh et al.	324	207.17	
	5,010,024	04/23/91	Allen et al.	438	659	
	5,020,219	06/04/91	Leedy	29	846	
	5,034,685	07/23/91	Leedy	324	158 F	
	5,070,026	12/03/91	Greenwald et al.	437	3	
	5,071,510	12/10/91	Findler et al.	156	647	
	5,098,865	03/24/92	Machado et al.	438	788	
	5,103,557	04/14/92	Leedy	29	832	
	5,110,373	05/05/92	Mauger	148	33.2	
	5,111,278	05/05/92	Eichelberger	357	75	
	5,116,777	05/26/92	Chan et al.	438	234	
	5,130,894	07/14/92	Miller	361	393	
	5,132,244	07/21/92	Roy	438	477	

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not conformance and not considered. Include copy of this form with next communication to applicant.

FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO. ELM-1 Cont. 10	APPLICATION NO. 10/700,429
	APPLICANT Glenn J. Leedy	CONFIRMATION NO. 5639
	FILING DATE November 3, 2003	GROUP 3729

	5,151,775	09/29/92	Hadwin	357	80	
	5,156,909	10/20/92	Henager, Jr. et al.	428	334	
	5,203,731	04/20/93	Zimmerman	445	24	
	5,225,771	07/06/93	Leedy	324	158	
	5,236,118	08/17/93	Bower et al.	228	193	
	5,262,351	11/16/93	Bureau et al.	437	183	
	5,270,261	12/14/93	Bertin et al.	437	209	
	5,273,940	12/28/93	Sanders	437	209	
	5,274,270	12/28/93	Tuckerman	257	758	
	5,279,865	01/18/94	Chebi et al.	427	574	
	5,284,796	02/08/94	Nakanishi et al.	437	183	
	5,323,035	06/21/94	Leedy	257	48	
	5,324,687	06/28/94	Wojnarowski	437	225	
	5,354,695	10/11/94	Leedy	438	411	
	5,363,021	11/08/94	MacDonald	315	366	
	5,385,632	01/31/95	Goossen	156	630	
	5,385,909	01/31/95	Nelson et al.	514	291	
	5,420,458	05/30/95	Shimoji	257	622	
	5,424,920	06/13/95	Miyake	361	735	
	5,426,072	06/20/95	Finnila	437	208	
	5,426,363	06/20/95	Akagi et al.	324	239	
	5,432,444	07/11/95	Yasohama et al.	324	240	
	5,432,729	07/11/95	Carson et al.	365	63	
	5,434,500	07/18/95	Hauck et al.	324	67	
	5,451,489	09/19/95	Leedy	430	313	
	5,453,404	09/26/95	Leedy	437	203	
	5,457,879	10/17/95	Gurtler et al.	29	895	
	5,476,813	12/19/95	Naruse	437	132	
	5,489,554	02/06/96	Gates	437	208	
	5,502,667	03/26/96	Bertin et al.	365	51	
	5,512,397	04/30/96	Leedy	430	30	
	5,527,645	06/18/96	Pati et al.	430	5	

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not conformance and not considered. Include copy of this form with next communication to applicant.

FORM PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. ELM-1 Cont. 10		APPLICATION NO. 10/700,429	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT				APPLICANT Glenn J. Leedy		CONFIRMATION NO. 5639	
				FILING DATE November 3, 2003		GROUP 3729	
	5,529,829	06/25/96	Koskenmaki et al.	428	167		
	5,534,465	07/09/96	Frye et al.	437	209		
	5,555,212	09/10/96	Toshiaki et al.	365	200		
	5,563,084	10/08/96	Ramm et al.	437	51		
	5,571,741	11/05/96	Leedy	437	51		
	5,580,687	12/03/96	Leedy	430	5		
	5,581,498	12/03/96	Ludwig et al.	365	63		
	5,582,939	12/10/96	Pierrat	430	5		
	5,583,688	12/10/96	Hornbeck	359	291		
	5,592,007	01/07/97	Leedy	257	347		
	5,592,018	01/07/97	Leedy	257	619		
	5,595,933	01/21/97	Heijboer	439	20		
	5,606,186	02/25/97	Noda	257	226		
	5,627,112	05/06/97	Tennant et al.	438	113		
	5,629,137	05/13/97	Leedy	430	313		
	5,633,209	05/27/97	Leedy	435	228		
	5,637,536	06/10/97	Val	438	686		
	5,654,127	08/05/97	Leedy	430	315		
	5,654,220	08/05/97	Leedy	438	25		
	5,656,552	08/12/97	Hudak et al.	438	15		
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	5,694,588	12/02/97	Ohara et al.	395	566		
	5,725,995	03/10/98	Leedy	430	315		
	5,750,211	05/12/98	Weise et al.	427	579		
	5,760,478	06/02/98	Bozso et al.	257	777		
	5,773,152	06/30/98	Okonogi	428	446		
	5,786,116	07/28/98	Rolfson	430	5		
	5,793,115	08/11/98	Zavracky et al.	257	777		
	5,831,280	11/03/98	Ray	257	48		
	5,834,334	11/10/98	Leedy	438	107		
	5,840,593	11/24/98	Leedy	438	6		
	5,856,695	01/05/99	Ito et al.	257	370		

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FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO. ELM-1 Cont. 10	APPLICATION NO. 10/700,429
	APPLICANT Glenn J. Leedy	CONFIRMATION NO. 5639
	FILING DATE November 3, 2003	GROUP 3729

	5,868,949	02/09/99	Sotokawa et al.	216	18	
	5,869,354	02/09/99	Leedy	438	110	
	5,870,176	02/09/99	Sweatt et al.	355	53	
	5,880,010	03/09/99	Davidson	438	455	
	5,882,532	03/16/99	Field et al.	216	2	
	5,902,118	05/11/99	Hübner	438	106	
	5,915,167	06/22/99	Leedy	438	108	
	5,946,559	08/31/99	Leedy	438	157	
	5,985,693	11/16/99	Leedy	438	107	
	5,998,069	12/07/99	Cutter et al.	430	5	
	6,008,126	12/28/99	Leedy	438	667	
	6,020,257	02/01/00	Leedy	438	626	
	6,045,625	04/04/00	Houston	148	33.3	
	6,084,284	07/04/00	Adamic, Jr.	257	506	
	6,097,096	08/01/00	Gardner et al.	257	777	
	6,133,640	10/17/00	Leedy	257	778	
	6,194,245 B1	02/27/01	Tayanaka	438	57	
	6,197,456 B1	03/06/01	Aleshin et al.	430	5	
	6,208,545 B1	03/27/01	Leedy	365	51	
	6,236,602 B1	05/22/01	Patti	365	201	
	6,261,728 B1	07/17/01	Lin	430	30	
	6,288,561 B1	09/11/01	Leedy	324	760	
	6,294,909 B1	09/25/01	Leedy	324	207.17	

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
	WO 98/19337	05/1998	PCT	H01L	21/44		
	GB 2,215,168	09/1989	UK	G09G	1/00		
	EP 0 189 976	08/1986	EPO	H01L	31/18		
	EP 0 731 525	09/1996	EPO	H01P	5/00		
	2641129	12/1988	France	H01L	39/04		
	JP 60-74643	04/1985	Japan			ABST	

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	JP 02-082564	03/1990	Japan
	JP 04-083371	03/1992	Japan
	JP 04-107964	04/1992	Japan
	JP 402027600A	01/1990	Japan

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER INITIAL	
	"IC Tower Patent: Simple Technology Receives Patent on the IC Tower, a Stacked Memory Technology," http://www.simpletech.com/whatsnew/memory/@60824.htm (1998).
	Alloert, K., et al., "A Comparison Between Silicon Nitride Films Made by PCVD of N ₂ -SiH ₄ /Ar and N ₂ -SiH ₄ /He," <i>Journal of the Electrochemical Society</i> , Vol. 132, No. 7, pp. 1763-1766, (July 1985).
	Hendricks, et al., "Polyquinoline Coatings and Films: Improved Organic Dielectrics for IC's and MCM's," <i>Eleventh IEEE/CHMT International Electronics Manufacturing Technology Symposium</i> , pp. 361-265 (1991).
	Knolle, W.R., et al., "Characterization of Oxygen-Doped, Plasma-Deposited Silicon Nitride," <i>Journal of the Electrochemical Society</i> , Vol. 135, No. 5, pp. 1211-1217, (May 1988).
	Nguyen, S.V., "Plasma Assisted Chemical Vapor Deposited Thin Films for Microelectronic Applications," <i>J. Vac. Sci. Technol.</i> Vol. B4, No. 5, pp.1159-1167, (Sep/Oct. 1986).
	Olmer, et al., "Intermetal Dielectric Deposition by Plasma Enhanced Chemical Vapor Deposition," <i>Fifth IEEE/CHMT International Electronic Manufacturing Technology Symposium - Design-to-Manufacturing Transfer Cycle</i> , pp. 98-99 (1988).
	Runyan, W.R., "Deposition of Inorganic Thin Films," <i>Semiconductor Integrated Circuit Processing Technology</i> , p. 142 (1990).
	Sze, S.M., "Surface Micromachining," <i>Semiconductor Sensors</i> , pp. 58-63 (1994).
	Vossen, John L., "Plasma-Enhanced Chemical Vapor Deposition," <i>Thin Film Processes II</i> , pp. 536-541 (1991).
	Wolf, Stanley, "Basics of Thin Films," <i>Silicon Processing for the VLSI Era</i> , pp. 115, 192, 193, and 199 (1986).

EXAMINER

DATE CONSIDERED

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